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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
10/811,973	03/30/2004	Toshiya Nozawa	843.43729X00	2994	
20457	7590 02/09/2006		EXAM	EXAMINER	
	LI, TERRY, STOUT & F	SANDVIK, BENJAMIN P			
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ARLINGTO	N, VA 22209-3873		2826		
			DATE MAILED: 02/09/2006	6	

Please find below and/or attached an Office communication concerning this application or proceeding.

Office Action Summary		Application No.	Applicant(s)				
		10/811,973	NOZAWA ET AL.	NOZAWA ET AL.			
		Examiner	Art Unit				
		Ben P. Sandvik	2826				
Period fo	The MAILING DATE of this communication app or Reply	ears on the cover sheet with	the correspondence ad	idress			
WHIC - External after - If NO - Failu Any	ORTENED STATUTORY PERIOD FOR REPLY CHEVER IS LONGER, FROM THE MAILING DATE of the may be available under the provisions of 37 CFR 1.13 SIX (6) MONTHS from the mailing date of this communication. It is period for reply is specified above, the maximum statutory period we re to reply within the set or extended period for reply will, by statute, reply received by the Office later than three months after the mailing and patent term adjustment. See 37 CFR 1.704(b).	ATE OF THIS COMMUNICA (6(a). In no event, however, may a reply rill apply and will expire SIX (6) MONTH: cause the application to become ABAN	TION. be timely filed from the mailing date of this component (35 U.S.C. § 133).				
Status							
1)⊠	Responsive to communication(s) filed on 12 De	ecember 2005					
	This action is FINAL . 2b) This action is non-final.						
3)							
,—	closed in accordance with the practice under Ex parte Quayle, 1935 C.D. 11, 453 O.G. 213.						
Dispositi	on of Claims						
4)🖂	☑ Claim(s) <u>1-21</u> is/are pending in the application.						
	4a) Of the above claim(s) <u>6 and 7</u> is/are withdrawn from consideration.						
	Claim(s) is/are allowed.						
·	Claim(s) <u>1-5 and 8-21</u> is/are rejected.						
·	Claim(s) is/are objected to.						
	8) Claim(s) are subject to restriction and/or election requirement.						
Applicati	on Papers						
9) The specification is objected to by the Examiner.							
10) The drawing(s) filed on is/are: a) accepted or b) objected to by the Examiner.							
Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).							
Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d).							
11) The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.							
Priority u	ınder 35 U.S.C. § 119						
12) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f). a) All b) Some * c) None of: 1. Certified copies of the priority documents have been received.							
	2. Certified copies of the priority documents have been received in Application No						
	3. Copies of the certified copies of the priority documents have been received in Application No						
	application from the International Bureau (PCT Rule 17.2(a)).						
* See the attached detailed Office action for a list of the certified copies not received.							
		·					
Attachmen	t(e)						
1) Notice of References Cited (PTO-892) 4) Interview Summary (PTO-413)							
2) Notice of Draftsperson's Patent Drawing Review (PTO-948) Paper No(s)/Mail Date							
	mation Disclosure Statement(s) (PTO-1449 or PTO/SB/08) r No(s)/Mail Date	5) Notice of Infor 6) Other:	mal Patent Application (PTC	D-152)			

DETAILED ACTION

Response to Arguments

Applicant's arguments filed 12/12/2005 have been fully considered but they are not persuasive. With respect to arguments towards claims 1 and 10, the Ochi reference does not limit the Dumet wire to Dumet wire Class 2. Furthermore, the examples of Table 1 given for the different Dumet wire classes in JISH4541 are merely examples and do not limit the use of any one Dumet wire to a specific application; all classes in Table 3 relate to using a Dumet wire in a glass sealed device. It is also noted that the copper ratios in Table 3 overlap between classes, suggesting that the classes are not mutually exclusive in application. Thus, one of ordinary skill in the art could consult the JISH4541 and decide to use a Dumet wire with a copper ratio of 20-25% in combination with the invention of Ochi.

With respect to arguments towards claim 18, that Inazawa does not teach a structure for sufficient adherence to glass, examiner respectfully submits that Ochi teaches a sufficient structure for adherence to glass, and the Inazawa reference is used to teach the certain thickness of a copper oxide layer which is well known in the art for different processes. Hence, the Ochi and Inazawa references in combination teach all of the limitations as recited in claim 18.

Applicant's arguments with respect to claim 5 have been considered but are moot in view of the new ground(s) of rejection.

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Claim Rejections - 35 USC § 102

The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

(b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.

Claims 1, 2, 10-13, 16, and 17 are rejected under 35 U.S.C. 102(b) as being anticipated by Ochi et al (U.S. Patent #6344790).

With respect to **claim 1**, Ochi teaches first and second electrodes having layers containing copper as main components (Fig. 4, 3A and 3B); a semiconductor element arranged between said first and second electrodes and electrically connected to said first and second electrodes (Fig. 4, 2); and a glass sealing member which seals said first electrode, said semiconductor element, and said second electrode (Fig. 4, 1); wherein, in the first and second electrodes, ratios of the layers containing copper as main components are not less than 20 wt% (Fig. 2, 12).

With respect to **claim 2**, Ochi teaches that said first and second electrodes are constituted by Dumet wires (Col 1 Ln 26).

With respect to **claim 10**, Ochi teaches first and second electrodes wherein the ratios said layers containing copper as main components fall within the range of 20 to 25 wt% (Col 1 Ln 26).

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With respect to **claim 11**, Ochi teaches first and second electrodes wherein the ratios said layers containing copper as main components fall within the range of 21 to 24 wt% (Col 1 Ln 26).

With respect to **claim 12**, Ochi teaches that said first and second electrodes have core portions (Fig. 2, 11) and said layers containing copper as main components, said layers being formed on the outer peripheries of said core portions (Fig. 2, 13).

With respect to **claim 13**, Ochi teaches that said core portions of said first and second electrodes comprise a nickel-containing alloy (Col 1 Ln 32).

With respect to **claim 16**, Ochi teaches that said core portions of said first and second electrodes are comprised of an alloy containing iron and nickel as main components (Col 1 Ln 32).

With respect to **claim 17**, Ochi teaches that said first and second electrodes have copper oxide layers formed on the outer peripheries of said layers containing copper as main components (Fig. 2, 13 and Col 1 Ln 33-34), the copper oxide layers contacting with said glass sealing member.

Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

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Claims 3, 5, 9, 14, and 15 are rejected under 35 U.S.C. 103(a) as being unpatentable over Ochi, in view of Robinson et al (U.S. Patent #4042951).

With respect to claim 3, Ochi teaches all of the limitations of claim 1, but does not teach that said semiconductor element is a diode. Robinson teaches a semiconductor device that is a diode (Col 1 Ln 53-56). It would have been obvious to one of ordinary skill in the art at the time the invention was made to provide the device of Ochi with a diode as taught by Robinson in order to adapt the device to diode functions.

With respect to claim 9, Ochi teaches all of the limitations of claim 1, but does not teach that the semiconductor element has a bump electrode; wherein the thickness of said layers containing copper as main components are larger than said thickness of said bump electrode. Robinson teaches a semiconductor element having a bump electrode (Fig. 1, 15), the thickness of copper containing layers being larger than the thickness of the bump electrode (Fig. 2, 31 and 32). It would have been obvious to one of ordinary skill in the art at the time the invention was made to make the device of Ochi with a semiconductor element having a bump electrode in order to improve the reliability of the connection to the Dumet electrode, and to make the thickness of the copper containing layers larger than the thickness of the bump electrode in order to maintain a small size of the package.

With respect to claim 14, Ochi teaches all of the limitations of claim 12, but does not teach that the nickel-containing alloy has a nickel content of 45 wt% Art Unit: 2826

or less. Robinson teaches a core portion comprised of a nickel-containing alloy having a nickel content of 45 wt% or less (Col 2 Ln 23-24). It would have been obvious to one of ordinary skill in the art at the time the invention was made to produce the core portion of Ochi with a nickel content of 45 wt% or less as taught by Robinson in order to control the resistance of the electrode.

With respect to **claim 15**, Ochi teaches all of the limitations of claim 12, but does not teach that the nickel-containing alloy has a nickel content of 41-43 wt% or less. Robinson teaches a core portion comprised of a nickel-containing alloy having a nickel content of 41-43 wt% or less (Col 2 Ln 23-24). It would have been obvious to one of ordinary skill in the art at the time the invention was made to produce the core portion of Ochi with a nickel content of 41-43 wt% or less as taught by Robinson in order to control the resistance of the electrode.

Claims 5 and 21 are rejected under 35 U.S.C. 103(a) as being unpatentable over Ochi and Robinson, in view of Sugimoto et al (U.S. Patent #6137211).

With respect to **claims 5 and 21**, Ochi teaches all of the limitations of claim 1, but does not teach that the semiconductor element has a metal electrode, wherein a sealing temperature of said glass sealing member is a temperature at which silicification of said metal electrode of the semiconductor element is not enhanced. Robinson teaches a semiconductor element with a metal electrode (Fig. 1, 15); and a sealing temperature of the glass sealing member (Col 3 Ln 17-20) is a temperature at which silicification of said metal

electrode is not enhanced. It would have been obvious to one of ordinary skill in the art at the time the invention was made to provide the device of Ochi with a semiconductor element having a metal electrode in order to make a reliable connection to the Dumet electrode, and to seal the glass member at a temperature at which silicification of said metal electrode is not enhanced in order to maintain the desired characteristics of the device. Sugimoto teaches a glass sealing member which is softened and sealed at a temperature within the range of 500 to 1000 degrees C (Col 3 Ln 1-5). It would have been obvious to one of ordinary skill in the art at the time the invention was made to seal the glass of Ochi and Robinson at a temperature of less than 630 degrees C as taught by Sugimoto in order prevent corrosion of the electrode.

Claim 6 is rejected under 35 U.S.C. 103(a) as being unpatentable over Ochi, in view of Sugimoto.

With respect to **claim 6**, Ochi does not teach a glass material (potassium oxide, Col 3 Ln 40) that has a glass softening point of 560° C or less. Sugimoto teaches a glass-sealing member which is softened and sealed at a temperature within the range of 500 to 1000 degrees C (Col 3 Ln 1-5). It would have been obvious to one of ordinary skill in the art at the time the invention was made to seal the glass of Ochi at a temperature of less than 630 degrees C as taught by Sugimoto in order prevent corrosion of the electrode.

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Claim 18 is rejected under 35 U.S.C. 103(a) as being unpatentable over Ochi in view of Inazawa et al (U.S. Patent #5372886).

With respect to **claim 18**, Ochi teaches all of the limitations of claim 17, but does not teach that the thickness of the copper oxide layers are 1.5 micrometers or less. Inazawa teaches a wire that is provided with a copper oxide layer that is 1 micrometer thick (Col 8 Ln 19-21). It would have been obvious to one of ordinary skill in the art at the time the invention was made to provide the wire electrode of Ochi with a copper oxide layer with a thickness of less than 1.5 micrometers as taught by Inazawa in order to improve the insulation of the wire.

Claims 19 and 20 are rejected under 35 U.S.C. 103(a) as being unpatentable over Ochi, in view of Einthoven (U.S. Patent #4742377).

With respect to **claims 19 and 20**, Ochi teaches all of the limitations of claim 1, but does not teach that said semiconductor element comprises by a Schottky barrier diode having: a semiconductor substrate; an epitaxial layer formed on the semiconductor substrate; and a metal electrode formed on the epitaxial layer. Einthoven teaches a semiconductor element comprising a Schottky barrier diode (abstract) having: a semiconductor substrate (Fig. 4, 11); an epitaxial layer formed on the semiconductor substrate (Fig. 4, 5); and a metal electrode formed on the epitaxial layer (Fig. 4, 13, 15, 17) having a tungsten film (Col 3 Ln 4). It would have been obvious to one of ordinary skill in the art at the

time the invention was made to provide the device of Ochi with a semiconductor device comprising a Schottky barrier diode as taught by Einthoven in order to use the device as a rectifier.

Conclusion

THIS ACTION IS MADE FINAL. Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).

A shortened statutory period for reply to this final action is set to expire THREE MONTHS from the mailing date of this action. In the event a first reply is filed within TWO MONTHS of the mailing date of this final action and the advisory action is not mailed until after the end of the THREE-MONTH shortened statutory period, then the shortened statutory period will expire on the date the advisory action is mailed, and any extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of the advisory action. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the mailing date of this final action.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Ben P. Sandvik whose telephone number is (571) 272-8446. The examiner can normally be reached on Mon-Fri.

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If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Nathan Flynn can be reached on (571) 272-1915. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic

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